

Chapter2-homework

- 2-1 For the circuit in Figure 0.2, $V_s = 3.3$ V. Assume $AD = 12\mu\text{m}^2$, $\phi_0 = 0.65$ V, and $m = 0.5$. $N_A = 2.5 \text{ E}16$ and $N_D = 5 \text{ E}15$.
 - **a.** Find I_D and V_D .
 - **b.** Is the diode forward- or reverse-biased?
 - **c.** Find the depletion region width, W_j , of the diode.
 - **d.** Use the parallel-plate model to find the junction capacitance, C_j .
 - **e.** Set $V_s = 1.5$ V. Again using the parallel-plate model, explain qualitatively why C_j increases.

homework

- 2-2 Determine the NMOS and PMOS mode of operation (saturation, linear, or cutoff) and drain current I_D for each of the biasing configurations given below. Verify with SPICE. Use the following transistor data: NMOS: $k'_n = 115\mu\text{A}/\text{V}^2$, $V_{T0} = 0.43\text{ V}$, $\lambda = 0.06\text{ V}^{-1}$, PMOS: $k'_p = 30\mu\text{A}/\text{V}^2$, $V_{T0} = -0.4\text{ V}$, $\lambda = -0.1\text{ V}^{-1}$. Assume $(W/L) = 1$.
 - a. NMOS: $V_{GS} = 2.5\text{ V}$, $V_{DS} = 2.5\text{ V}$. PMOS: $V_{GS} = -0.5\text{ V}$, $V_{DS} = -1.25\text{ V}$.
 - b. NMOS: $V_{GS} = 3.3\text{ V}$, $V_{DS} = 2.2\text{ V}$. PMOS: $V_{GS} = -2.5\text{ V}$, $V_{DS} = -1.8\text{ V}$.
 - c. NMOS: $V_{GS} = 0.6\text{ V}$, $V_{DS} = 0.1\text{ V}$. PMOS: $V_{GS} = -2.5\text{ V}$, $V_{DS} = -0.7\text{ V}$.

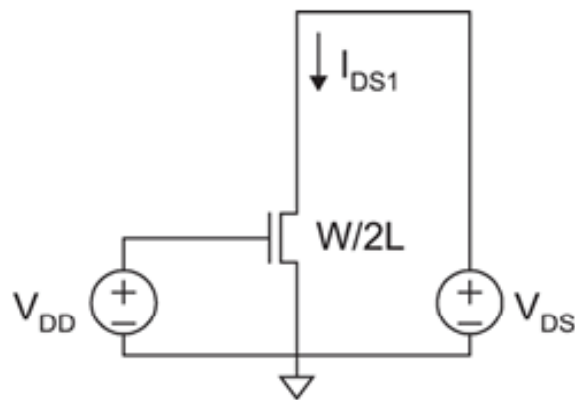
homework

- 2-3 Given the data in Table 0.1 for a short channel NMOS transistor with $V_{DSAT} = 0.6$ V and $k' = 100$ $\mu\text{A}/\text{V}^2$, calculate V_{T0} , γ , λ , $2|\phi_f|$, and W / L :

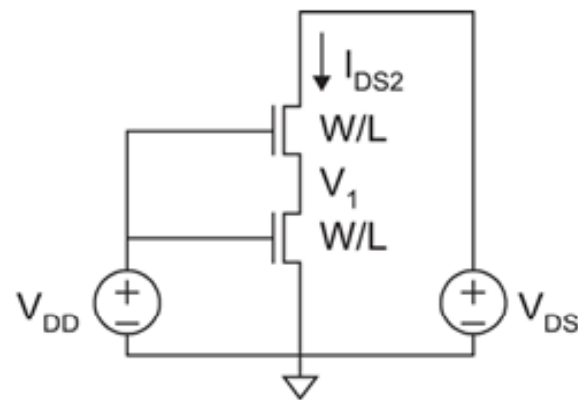
	V_{GS}	V_{DS}	V_{BS}	I_D (μA)
1	2.5	1.8	0	1812
2	2	1.8	0	1297
3	2	2.5	0	1361
4	2	1.8	-1	1146
5	2	1.8	-2	1039

homework

- 2-4 show that the current through two transistors in series is equal to the current through a single transistor of twice the length if the transistors are well described by the shockley mode. specifically show that $I_{DS1} = I_{DS2}$ in figure below when the transistors are in their linear region: $V_{DS} < V_{DD} - V_T$, $V_{DD} > V_T$ (this is also true in saturation)



(a)



(b)

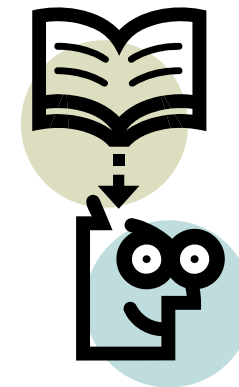
Homework

- 2-5 prove the formula

$$I_D = \frac{\mu_n C_{ox}}{1 + (V_{DS}/L\xi_c)} \frac{W}{L} \left[(V_{GS} - V_T)V_{DS} - \frac{V_{DS}^2}{2} \right]$$

$$= \mu_n C_{ox} \frac{W}{L} \left[(V_{GS} - V_T)V_{DS} - \frac{V_{DS}^2}{2} \right] \kappa(V_{DS})$$

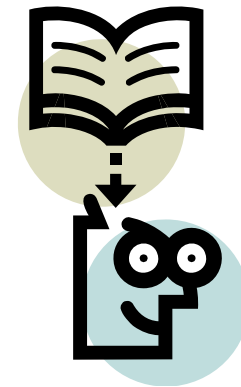
$$\kappa(V) = \frac{1}{1 + V/L\xi_c}$$



Velocity Saturation

- 2-6 prove the formula

$$V_{DSAT} = K(V_{GT})V_{GT}$$



homework

- 2-7 calculate the diffusion parasitic C_{db} of the drain of a unit-sized contacted nMOS transistor in a 0.6 μm process when the drain is at 0 and at $V_{DD}=5\text{V}$. Assume the substrate is grounded. the transistor characteristics are :

$C_{J0}=0.42\text{fF}/\mu\text{m}^2$, $M_J=0.44$, $C_{JSW0}=0.33\text{fF}/\mu\text{m}$, $M_{JSW}=0.12$ and $\psi_0=0.98\text{V}$ at room temperature

homework

- 2-8 consider the nMOS transistor in a 0.6 μ m process with gate oxide thickness of 100 \AA , the doping level is $N_A=2*10^{17}\text{cm}^{-3}$ and the nominal threshold voltage is 0.7V. The body is tied to ground with a substrate contact. How much does the threshold change at room temperature if the source is at 4V instead of 0